

PATENT
2224-0163P



IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant:	Tatsuya NAKANO	Conf.:	5816
Appl. No.:	09/463,059	Group:	1752
Filed:	January 19, 2000	Examiner:	Y. CLARKE
For:	ACID-SENSITIVE COMPOUND AND RESIN COMPOSITION FOR PHOTORESIST		

LARGE ENTITY TRANSMITTAL FORM

Assistant Commissioner for Patents
Washington, DC 20231

July 26, 2001

RECEIVED
JUL 31 2001
TC 1700 MAIL ROOM

Sir:

Transmitted herewith is an amendment in the above-identified application.

- ☐ The enclosed document is being transmitted via the Certificate of Mailing provisions of 37 C.F.R. § 1.8.
- ☐ The enclosed document is being transmitted via facsimile.

The fee has been calculated as shown below:

	CLAIMS REMAINING AFTER AMENDMENT		HIGHEST NUMBER PREVIOUSLY PAID FOR		PRESENT EXTRA	RATE	ADDITIONAL FEE
TOTAL	14	-	20	=	0	\$18	\$0.00
INDEPENDENT	1	-	3	=	0	\$80	\$0.00
<input type="checkbox"/> FIRST PRESENTATION OF A MULTIPLE DEPENDENT CLAIM						\$270	\$0.00
						TOTAL	\$0.00

- ☐ Petition for () month(s) extension of time pursuant to 37 C.F.R. §§ 1.17 and 1.136(a). \$0.00 for the extension of time.
- ☐ No fee is required.
- ☒ A check in the amount of \$110.00 is enclosed for Terminal Disclaimer fee.
- ☐ Please charge Deposit Account No. 02-2448 in the amount of \$0.00. This form is submitted in triplicate.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. § 1.16 or under 37 C.F.R. § 1.17; particularly, extension of time fees.

Respectfully submitted,

BIRCH, STEWART, KOLASCH & BIRCH, LLP

By Edward H. Valance #19896
~~for~~ Raymond C. Stewart, #21,066

RCS/EHV/jms
2224-0163P

P.O. Box 747
Falls Church, VA 22040-0747
(703) 205-8000

ATTACHMENT

(Rev. 01/22/01)



PATENT
2224-0163P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Tatsuya NAKANO Conf.: 5816
Appl. No.: 09/463,059 Group: 1752
Filed: January 19, 2000 Examiner: Y. CLARKE
For: ACID-SENSITIVE COMPOUND AND RESIN
COMPOSITION FOR PHOTORESIST

RECEIVED
JUL 31 2001
TC 1700 MAIL ROOM

AMENDMENT

Assistant Commissioner for Patents
Washington, DC 20231

July 28, 2001

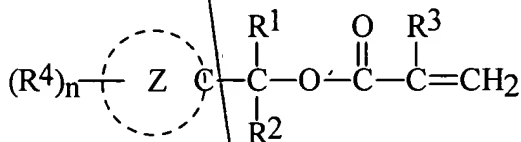
Sir:

In reply to the Examiner's Office Action dated April 27, 2001, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

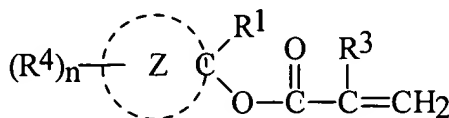
In the Claims:

Please amend claim 1 as follows:

1. (Amended) An acid-responsive compound represented by the following formula (1) or (2)



(1)



(2)